[ABSTRACT]

~~A substrate treatment device according~~According to one aspect of the technique of the present ~~invention~~disclosure, there is provided ~~with: a~~ a substrate processing apparatus including a nozzle ~~that is~~ arranged along an inner wall surface of a ~~treatment container~~process vessel and ~~that is~~ provided at least in a lower portion of the process vessel with a gap ~~from~~ between the nozzle and the inner wall surface of the ~~treatment container at least at a lower section of said treatment container~~process vessel; a nozzle base ~~section that supports~~supporting the nozzle and ~~that has, in the interior thereof,~~accommodating therein a flow ~~passage~~path communicating with the nozzle; a support ~~member that is~~structure provided along the inner wall surface and ~~that is~~ joined to a first ~~joining~~joint surface of the nozzle base ~~section, said first joining surface~~that does not ~~facing~~face the inner wall surface; and a ~~slope~~ tilt-adjusting ~~tool configured to be capable of~~structure for adjusting ~~the slope~~a tilt of the nozzle base ~~section~~ at a position ~~displaced~~shifted toward ~~the~~a center of the ~~treatment container with respect to the~~process vessel and away from a center of gravity of a nozzle assembly ~~including~~comprising the nozzle and the nozzle base ~~section~~.